## Vittorio Privitera

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/6985040/publications.pdf

Version: 2024-02-01

27 1,579 22 papers citations h-index

526287 27 g-index

27 27 all docs citations

27 times ranked 2157 citing authors

#	Article	IF	CITATIONS
1	ZnO for application in photocatalysis: From thin films to nanostructures. Materials Science in Semiconductor Processing, 2017, 69, 44-51.	4.0	244
2	Ag/TiO2 nanocomposite for visible light-driven photocatalysis. Superlattices and Microstructures, 2018, 123, 394-402.	3.1	122
3	Photocatalytical and antibacterial activity of TiO2 nanoparticles obtained by laser ablation in water. Applied Catalysis B: Environmental, 2015, 165, 487-494.	20.2	109
4	Low temperature atomic layer deposition of ZnO: Applications in photocatalysis. Applied Catalysis B: Environmental, 2016, 196, 68-76.	20.2	98
5	Photocatalytic activity of CuO and Cu2O nanowires. Materials Science in Semiconductor Processing, 2016, 42, 89-93.	4.0	91
6	Graphene oxide and titania hybrid Nafion membranes for efficient removal of methyl orange dye from water. Carbon, 2015, 82, 489-499.	10.3	86
7	Selective photodegradation of paracetamol by molecularly imprinted ZnO nanonuts. Applied Catalysis B: Environmental, 2018, 238, 509-517.	20.2	84
8	Trap-Limited Migration of Si Self-Interstitials at Room Temperature. Physical Review Letters, 1996, 76, 1493-1496.	7.8	79
9	Immobilization of nanomaterials in PMMA composites for photocatalytic removal of dyes, phenols and bacteria from water. Journal of Photochemistry and Photobiology A: Chemistry, 2016, 321, 1-11.	3.9	71
10	A phase-field approach to the simulation of the excimer laser annealing process in Si. Journal of Applied Physics, 2004, 95, 4806-4814.	2.5	69
11	Depth profiles of vacancy- and interstitial-type defects in MeV implanted Si. Journal of Applied Physics, 1997, 81, 1639-1644.	2.5	67
12	An enhanced photocatalytic response of nanometric TiO <sub>2</sub> wrapping of Au nanoparticles for eco-friendly water applications. Nanoscale, 2014, 6, 11189-11195.	5.6	58
13	N-type doping of Ge by As implantation and excimer laser annealing. Journal of Applied Physics, 2014, 115, .	2.5	57
14	Black TiOx photocatalyst obtained by laser irradiation in water. Catalysis Communications, 2016, 84, 11-15.	3.3	42
15	B-doping in Ge by excimer laser annealing. Journal of Applied Physics, 2013, 113, .	2.5	37
16	Photocatalytic and antibacterial properties of titanium dioxide flat film. Materials Science in Semiconductor Processing, 2016, 42, 32-35.	4.0	32
17	Enhancing carrier generation in TiO <sub>2</sub> by a synergistic effect between plasmon resonance in Ag nanoparticles and optical interference. Nanoscale, 2015, 7, 13468-13476.	5 <b>.</b> 6	31
18	Depth distribution of B implanted in Si after excimer laser irradiation. Applied Physics Letters, 2005, 86, 051909.	3.3	29

#	ARTICLE	IF	CITATIONS
19	Low temperature deactivation of Ge heavily n-type doped by ion implantation and laser thermal annealing. Applied Physics Letters, 2017, 110, .	3.3	27
20	Laser annealing in Si and Ge: Anomalous physical aspects and modeling approaches. Materials Science in Semiconductor Processing, 2017, 62, 80-91.	4.0	25
21	A Spreading Resistanceâ€Based Technique for Twoâ€Dimensional Carrier Profiling. Journal of the Electrochemical Society, 1993, 140, 262-270.	2.9	22
22	Anomalous transport of Sb in laser irradiated Ge. Applied Physics Letters, 2012, 101, 172110.	3.3	22
23	Vacancy generation in liquid phase epitaxy of Si. Physical Review B, 2007, 75, .	3.2	20
24	Au thin films nano-structuration on polycrystalline anatase and rutile TiO2 substrates towards photocatalytic applications. Materials Science in Semiconductor Processing, 2016, 42, 40-44.	4.0	17
25	Impurity and defect interactions during laser thermal annealing in Ge. Journal of Applied Physics, 2016, 119, .	2.5	15
26	Role of oxygen on the electrical activation of B in Ge by excimer laser annealing. Physica Status Solidi (A) Applications and Materials Science, 2014, 211, 122-125.	1.8	13
27	Oxygen behavior in germanium during melting laser thermal annealing. Materials Science in Semiconductor Processing, 2016, 42, 196-199.	4.0	12